

**RETICLE CHUCKS AND METHODS FOR HOLDING A LITHOGRAPHIC
RETICLE UTILIZING SAME**

Abstract of the Disclosure

5 Reticle-holding devices ("reticle chucks") are disclosed that define a downstream-facing reticle-mounting surface configured for holding an upstream-facing surface of a reticle for use in a microlithography apparatus. The reticle chucks can include peripheral regions and struts that define respective portions of the reticle-mounting surface, thereby preventing reticle sag while still allowing the
10 axial distance from the reticle to a projection-optical system to be measured by grazing incidence without obstruction. The reticle can be held by, e.g., electrostatic attraction or vacuum suction to the reticle-mounting surface. The subject chucks also can be used for holding a reticle blank while inscribing a pattern on the reticle blank.
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